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(54) Title: DEVELOPER TOLERANCE RESIST UNDERLAYER COMPOSITION AND METHOD FOR MANUFACTURING
RESIST PATTERN

(57) Abstract: A developer tolerance resist underlayer composition comprising a polymer (A), a cross-linking agent (B), a thermal acid generator (C) and a solvent (D); wherein the polymer (A) comprises at least a unit having a protective group that is deprotected by an acid, and the hydrophilicity of the portion where the deprotected unit is present changes after exposure.



WO 2024/017921 A1